

ABSTRACT

A lithographic projection apparatus including an interferometer system having a reach extending over a first, measurement station and a second, exposure station. The apparatus stores the position of the mask relative to the mask table initially. A wafer table may be transferred from the first, measurement station to the second, exposure station while fully under the control of the interferometer system. The critical path through the exposure station may then be reduced. The apparatus stores the position of the wafer relative to the wafer table at the measurement station. Subsequent alignment in the exposure station may then be performed in a shorter time as the position of the mask relative to a mask table is known.